

<b>FORM PTO-1449/A and B (Modified)</b>  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>				APPLICATION NO.: Unassigned		ATTY. DOCKET NO.: S1022/8827	
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				APPLICANT: Cesare CLEMENTI et al.			
				GROUP ART UNIT: Unassigned		EXAMINER: Unassigned	
Sheet	1	of	1				

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#### U.S. PATENT DOCUMENTS

Examiner's Initials#	Cite No.	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication or of issue of Cited Document MM-DD-YYYY
		Number	Kind Code		
NA		4,471,373		Shinji Shimizu, et al.	09/11/84
		4,780,424		Mark A. Holler et al.	10/25/88
		5,104,819		Philip E. Freiburger et al.	04/14/92
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#### FOREIGN PATENT DOCUMENTS

Examiner's Initials#	Cite No.	Foreign Patent Document			Name of Patentee or Applicant of Cited Document (not necessary)	Date of Publication of Cited Document MM-DD-YYYY	Translation (Y/N)
		Office/Country	Number	Kind Code			

#### OTHER ART — NON PATENT LITERATURE DOCUMENTS

Examiner's Initials#	Cite No	Include name of the author (in CAPITAL LETTERS) title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, relevant page(s), volume-issue number(s), publisher, city and/or country where published.	Translation (Y/N)
NA		European Search Report from European Patent Application 95830282.0, filed June 30, 1995	
NA		IEEE IEDM Technical Digest 93, 1993 pp 321-324, Hsing-Huang Tseng et al., "Thin CVD Stacked Gate Dielectric For ULSI Technology"	

EXAMINER <i>[Signature]</i>	DATE CONSIDERED 4/26/04
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#EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.